

# Oxidation Furnace (LP)

Designed to improve the surface passivation properties of silicon solar cells by forming silicon dioxide(SiO<sub>2</sub>) and it lead to increase the efficiency.

## SOLAR TECHNOLOGY CELL PROCESS MACHINE

### Technical Specification

Format(mm)	3,300(W) x 7,805(L) x 3,570(H)
Gas Supply	N <sub>2</sub> , O <sub>2</sub>
Number of Chamber	10
Cycle Time(min)	50
Uptime(%)	99
Breakage Rate(%)	0.2
Wafer Throughput(wafers/hr)	16,800
Number of Boat per System	20
Wafer Pitch(mm)	2.38
Slots for Process Wafers	1,400 wafers/boat (Back to Back)
Cell Type	Monocrystalline, Multicrystalline Silicon wafers
Cell Size(mm)	M2(156*156) ~ M8(185*185)
Process Temperature(°C)	600 ~ 700
Process Pressure(mbar)	≥ 950

### Dimension

